

# RafaÅ, Chodun

## List of Publications by Year in descending order

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45  
papers

547  
citations

567281

15  
h-index

713466

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g-index

46  
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46  
docs citations

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times ranked

528  
citing authors

#	ARTICLE	IF	CITATIONS
1	Characterization of microstructural, mechanical and optical properties of TiO <sub>2</sub> layers deposited by GIMS and PMS methods. <i>Surface and Coatings Technology</i> , 2015, 282, 16-23.	4.8	44
2	Diamond, graphite, and graphene oxide nanoparticles decrease migration and invasiveness in glioblastoma cell lines by impairing extracellular adhesion. <i>International Journal of Nanomedicine</i> , 2017, Volume 12, 7241-7254.	6.7	33
3	Gas injection as a tool for plasma process control during coating deposition. <i>Surface and Coatings Technology</i> , 2013, 228, S367-S373.	4.8	31
4	Chemical and structural characterization of tungsten nitride (WN <sub>x</sub> ) thin films synthesized via Gas Injection Magnetron Sputtering technique. <i>Vacuum</i> , 2019, 165, 266-273.	3.5	28
5	Optical TiO <sub>2</sub> layers deposited on polymer substrates by the Gas Injection Magnetron Sputtering technique. <i>Applied Surface Science</i> , 2019, 466, 12-18.	6.1	27
6	Dependence of the specific features of two PAPVD methods: Impulse Plasma Deposition (IPD) and Pulsed Magnetron Sputtering (PMS) on the structure of Fe-Cu alloy layers. <i>Applied Surface Science</i> , 2013, 275, 14-18.	6.1	23
7	Copper nitride layers synthesized by pulsed magnetron sputtering. <i>Thin Solid Films</i> , 2018, 645, 32-37.	1.8	23
8	Phase composition of copper nitride coatings examined by the use of X-ray diffraction and Raman spectroscopy. <i>Journal of Molecular Structure</i> , 2018, 1165, 79-83.	3.6	22
9	Relation between modulation frequency of electric power oscillation during pulse magnetron sputtering deposition of MoN <sub>x</sub> thin films. <i>Applied Surface Science</i> , 2018, 456, 789-796.	6.1	19
10	Properties of TiN coatings deposited by the modified IPD method. <i>Vacuum</i> , 2010, 85, 514-517.	3.5	18
11	Peculiar Role of the Metallic States on the Nano-MoS <sub>2</sub> Ceramic Particle Surface in Antimicrobial and Antifungal Activity. <i>International Journal of Applied Ceramic Technology</i> , 2015, 12, 885-890.	2.1	18
12	The state of coating-substrate interfacial region formed during TiO <sub>2</sub> coating deposition by Gas Injection Magnetron Sputtering technique. <i>Surface and Coatings Technology</i> , 2020, 398, 126092.	4.8	18
13	Electric field used as the substitute for ultrasounds in the liquid exfoliation of hexagonal boron nitride. <i>Microelectronic Engineering</i> , 2014, 126, 124-128.	2.4	17
14	Novel GIMS technique for deposition of colored Ti/TiO <sub>2</sub> coatings on industrial scale. <i>Materials Science-Poland</i> , 2016, 34, 137-141.	1.0	16
15	Plasmochemical investigations of DLC/WC <sub>x</sub> nanocomposite coatings synthesized by gas injection magnetron sputtering technique. <i>Diamond and Related Materials</i> , 2019, 96, 1-10.	3.9	15
16	The sputtering of titanium magnetron target with increased temperature in reactive atmosphere by gas injection magnetron sputtering technique. <i>Applied Surface Science</i> , 2022, 574, 151597.	6.1	15
17	Optimization of gas injection conditions during deposition of AlN layers by novel reactive GIMS method. <i>Materials Science-Poland</i> , 2014, 32, 171-175.	1.0	14
18	Characterization of sp <sup>3</sup> bond content of carbon films deposited by high power gas injection magnetron sputtering method by UV and VIS Raman spectroscopy. <i>Spectrochimica Acta - Part A: Molecular and Biomolecular Spectroscopy</i> , 2018, 194, 136-140.	3.9	14

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19	Design of pulsed neon injection in the synthesis of W-B-C films using magnetron sputtering from a surface-sintered single powder cathode. <i>Thin Solid Films</i> , 2020, 716, 138426.	1.8	14
20	Influence of generation control of the magnetron plasma on structure and properties of copper nitride layers. <i>Thin Solid Films</i> , 2020, 694, 137731.	1.8	12
21	Synthesis of Copper Nitride Layers by the Pulsed Magnetron Sputtering Method Carried out under Various Operating Conditions. <i>Materials</i> , 2021, 14, 2694.	2.9	11
22	Impulse Plasma In Surface Engineering - a review. <i>Journal of Physics: Conference Series</i> , 2014, 564, 012007.	0.4	10
23	Structure of Cu <sup>+</sup> N layers synthesized by pulsed magnetron sputtering with variable frequency of plasma generation. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , 2017, 409, 167-170.	1.4	8
24	TiO <sub>2</sub> coating fabrication using gas injection magnetron sputtering technique by independently controlling the gas and power pulses. <i>Thin Solid Films</i> , 2021, 728, 138695.	1.8	8
25	On coating adhesion during impulse plasma deposition. <i>Physica Scripta</i> , 2014, T161, 014063.	2.5	7
26	OES studies of plasmoids distribution during the coating deposition with the use of the Impulse Plasma Deposition method controlled by the gas injection. <i>Vacuum</i> , 2016, 128, 259-264.	3.5	7
27	TiO <sub>2</sub> - based decorative interference coatings produced at industrial conditions. <i>Thin Solid Films</i> , 2020, 711, 138294.	1.8	7
28	Surface sintering of tungsten powder targets designed by electromagnetic discharge: A novel approach for film synthesis in magnetron sputtering. <i>Materials and Design</i> , 2020, 191, 108634.	7.0	7
29	Influence of modulation frequency on the synthesis of thin films in pulsed magnetron sputtering processes. <i>Materials Science-Poland</i> , 2018, 36, 697-703.	1.0	7
30	Computational modelling of discharges within the impulse plasma deposition accelerator with a gas valve. <i>Physica Scripta</i> , 2014, T161, 014049.	2.5	6
31	Methods of optimization of reactive sputtering conditions of Al target during AlN films deposition. <i>Materials Science-Poland</i> , 2015, 33, 894-901.	1.0	6
32	Reactive sputtering of titanium compounds using the magnetron system with a grounded cathode. <i>Thin Solid Films</i> , 2017, 640, 73-80.	1.8	6
33	Synthesis of multicomponent metallic layers during impulse plasma deposition. <i>Materials Science-Poland</i> , 2015, 33, 841-846.	1.0	5
34	Multi-sided metallization of textile fibres by using magnetron system with grounded cathode. <i>Materials Science-Poland</i> , 2017, 35, 639-646.	1.0	5
35	The role of magnetic energy on plasma localization during the glow discharge under reduced pressure. <i>Nukleonika</i> , 2016, 61, 191-194.	0.8	4
36	Application of the plasma surface sintering conditions in the synthesis of ReB <sup>+</sup> Ti targets employed for hard films deposition in magnetron sputtering technique. <i>International Journal of Refractory Metals and Hard Materials</i> , 2022, 103, 105756.	3.8	4

#	ARTICLE	IF	CITATIONS
37	Design of thin DLC/TiO <sub>2</sub> film interference coatings on glass screen protector using a neon-argon-based gas injection magnetron sputtering technique. <i>Diamond and Related Materials</i> , 2022, 123, 108859.	3.9	4
38	Morphology of the TiN coatings obtained by the IPD method with two frequencies of impulse plasma generation. <i>Surface and Coatings Technology</i> , 2010, 205, S28-S31.	4.8	3
39	Characteristic STATE of substrate and coatings interface formed by Impulse Plasma Deposition method. <i>Thin Solid Films</i> , 2018, 663, 25-30.	1.8	3
40	Titanium nitride coatings synthesized by IPD method with eliminated current oscillations. <i>Materials Science-Poland</i> , 2016, 34, 523-528.	1.0	2
41	The Microstructure and Properties of Carbon Thin Films on Nanobainitic Steel. <i>Metallurgical and Materials Transactions A: Physical Metallurgy and Materials Science</i> , 2021, 52, 5066-5078.	2.2	2
42	Structure of AlN films deposited by magnetron sputtering method. <i>Materials Science-Poland</i> , 2015, 33, 639-643.	1.0	1
43	The application of magnetic self-filter to optimization of AlN film growth process during the impulse plasma deposition synthesis. <i>Materials Science-Poland</i> , 2016, 34, 126-131.	1.0	1
44	Zastosowanie metody IPD do syntezy warstw c-AlN. <i>Elektronika</i> , 2014, 1, 15-17.	0.0	0
45	Influence of annealing on electronic properties of thin AlN films deposited by magnetron sputtering method on silicon substrates. , 2019, , .		0